

## DATA SHEET NexSil<sup>TM</sup> 20A

## NexSil™ 20A Colloidal Silica In Water

#### PRODUCT DESCRIPTION

NexSil 20A is an acidic dispersion of 20 nm colloidal silica at 30% concentration. The product is a clear liquid composed of highly uniform, spherical silica particles. The product has a slightly negative charge and is essentially free of Cl and sulfate ions.

The product finds use as a low sodium colloidal silica binder in investment casting and fibrous refractory applications. In catalyst formulations, the product provides a low sodium, high surface area source of silica and can be used to formulate catalyst support structures.

In electroplating applications, NexSil 20A is an excellent choice for use with trivalent chromium conversion coatings. The conversion coating is designed to bond with zinc or cadmium surfaces and the conversion coating containing NexSil 20A is applied immediately after the parts emerge from the electroplating bath. The colloidal silica improves corrosion resistance and abrasion resistance of the conversion coating.

#### TYPICAL PROPERTIES

Appearance: Translucent Sol  $SiO_2$  Content, %: 29 - 31 Water, %: 69 - 71 Particle Size, nm: 16 - 24 pH: 2.5 - 3.0 Surface Chemistry: Anionic

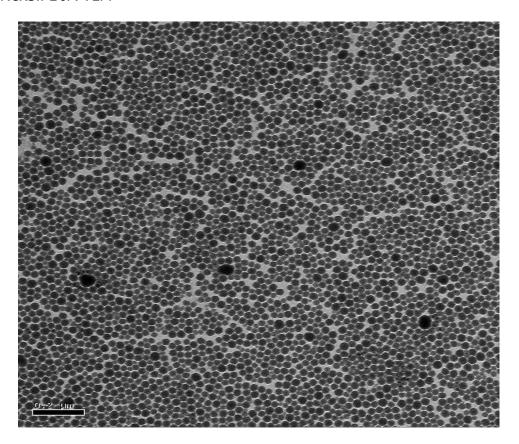
### TYPICAL IMPURITIES, AS IS BASIS

Sodium, ppm: <300 lron, ppm: 35 Aluminum, ppm: 300



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### FOR ADDITIONAL INFORMATION OR TO PLACE AN ORDER

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